## **Professional\_Summary:**

**8 years** of experience as a Memory Layout designer in ST Microelectronics (Subcontractor through Zia Semiconductor Pvt Ltd).

- Experience in Planning and development of layout activities (including time and resource allocation).
- Professional experience in development of layout of basic leaf cells in FDSOI 28nm, 40nm,
  65nm and 90nm technologies.
- Basic Layout training in FINFET 7nm and FDSOI 14nm.
- Experience in Development of Custom Cuts and Compiler products along with verifications like DRC/LVS, DFMs such as LFD, OPC, VRC and other top-level checks like Abstract checks, Library checks, etc. needed in QA before final delivery.
- Experience in Delivery of test chip cuts, Prelim/Final LEF and Compiler Products.

### **HIGHLIGHTS**

- 1. Excellent in leaf cell layout development of I/O and ROWDECODER.
- 2. Hands on experience in compiler development from scratch to delivery.
- 3. Very Good understanding of EM/IR issues and their corrections.
- 4. Good knowledge of layout effects like WPE, STI, LOD, Latch up and Antenna effect.
- 5. Understanding of different types of Memory architecture and floor planning.
- 6. Good Understanding of schematics and netlists.

#### **TECHNICAL Skills**

Layout Design	Cadence Virtuoso, ICFB and Synopsys Custom Compiler	
Verification (DRC/LVS)	Mentor graphics - Calibre	
Top-level Verifications	Crossfire Tool, ADOC tool	
Scripting Knowledge	Unix, Shell and Cadence Virtuoso skill	
Extraction	Star_rcxt	
EM/IR simulation	Customsim	

#### **SOFT Skills**

- Successfully managed a project leading a team of 5 and delivered it on time.
- Regularly Communicating with code and standard cell team for activities like programming cells and debugging cut development/generation.
- Actively provide guidance and support to juniors.

## **Professional experience in SRAM Memory Layouts:**

**Techno Node: 28nm FDSOI (STM Process)** 

Types of Compilers: SPHD, SPHS, DPHD, PRF2HD with HP, BB and LL variants.

#### Projects:

- Implementing HV marker for both GEONEXT and SAMSUNG compilers supporting Body bias up to 1.1V.
- SPHD mux 8 cut development from SPHS compiler (bit cell change).
- Implementing SCAN-CHAIN in PRF2HD compiler in both IO and CTRL blocks.
- SPHS compiler development from scratch.
- Feature addition and Design changes in PRF2HD, SPHDULV compilers.
- Bugfix and Implementation of Retention in SPL1 CACHE compiler.
- DRC/DFM updates in multiple compilers.

#### Responsibilities:

- Planning and overlooking all layout activities in last project leading a team of 5
- Development of LIO blocks in multiple compilers
- Development of ROWDECODER, Dummy Row dec and Redundancy Row dec.
- Development of DCOL block and ARRAY power cells.
- Design changes and updates in CTRL block.
- Provide Extraction of Leaf cells.
- EM and IR improvements.
- Final verifications (compiler level DRC/LVS/DFMs).
- Prelim, test chip and Final product delivery.

#### Challenges:

- Understanding different type of flavors in compilers like HP, BB and LL in flip well/traditional well with LVT, SVT and HVT layers. Performing verifications.
- Cut development from scratch and its LVS.
- Cut list improvement in SPHS compiler to cover all possible range and parameters.
- Placement and routing of IO block in reduced width since SPHD bit cell is used inside SPHS architecture. Critical nodes matching and signal shielding.

#### **Techno Node: 40nm (STM process)**

#### Projects:

- Porting of SPHS compiler to SPHSHD compiler.
- CMOSM40 SPHD\_ULV compiler development from scratch.
- Design changes and DRC/DFM updates in multiple compilers.

#### Responsibilities:

- Development of GIO and GCTRL blocks.
- Development of Redundancy ROWDEC and Retention block.
- Management of Power cells in DCOL and Core array.
- EM and IR improvements.
- Final verifications (compiler level DRC/LVS/DFMs).
- Prelim, test chip and Final product delivery.

#### Challenges:

• Regular and DFM improved layout with poly alignment across different blocks.

## Techno Nodes: 65nm, 90nm (STM process)

#### Projects:

- Latch up corrections in DPHD 65nm.
- Compiler development in BCD9S.
- DRC/DFM updates in multiple compilers.

#### Responsibilities:

- Strap insertion in CTRL, I/O and Bit cell array for DPHD 65nm.
- Development of I/O block in 90nm.
- Top level verifications and Product delivery.

#### Challenges:

- LVS issues in bit cell array.
- First Project delivery experience.

# Techno node: 7nm FinFet (Samsung aligned process) and 14nm FDSOI (STM process).

#### Zia Semiconductor internal projects for training.

- Knowledge of critical DRCs of base layers and metal layers.
- Leaf cell Layout development of Mux4 IO in 7nm and ROWDEC in 14nm.
- Understanding of dual patterning and associated metal DRCs.

# **Academic Qualifications:**

Education	UNIVERSITY/ BOARD	Year of Passing	Percentage
BTech (E&C)	JMI	2012	7.57 (CPI)
XII Standard	ISC Board	2008	86.83%
X Standard	ICSE Board	2006	84.5%